

# 軟X線を用いた 高エネルギー $\gamma$ 線発生

NewSUBARU蓄積リングを用いたアンジュレータ-光反射実験

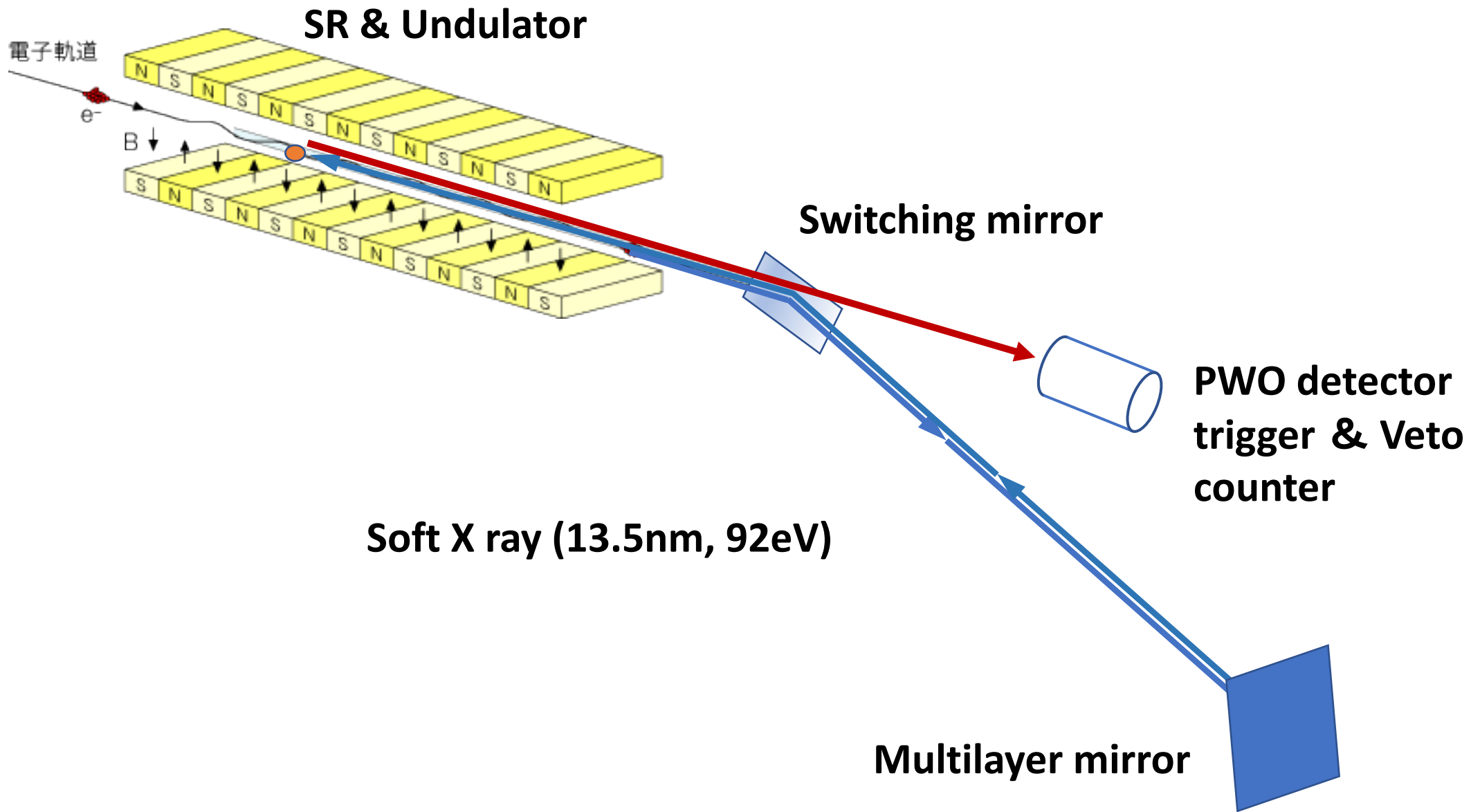
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清水、岡部、原田、渡邊、村松

# Outline

- Purpose
- NewSUBARU StorageRing
- Undulator spectrum
- Gamma-ray spectrum
- Multilayer mirror
- $\gamma$  ray production efficiency
- Experimental setup
- Schedule
- Expansion to 6GeV? - > Mr. Okuma?
- Problem

# Purpose

- Production of the high energy  $\gamma$ -ray by the inversed Compton scattering - returned soft X-rays by the multilayer mirror reflection from the undulator to the storage ring, collide with high energy electrons.
- Search for the possibility of  $\gamma$ -ray experiment with higher energy than LEPS/LEPS2 toward SPring-8-II (6 GeV).
- After confirming the generation of gamma rays, we obtain information such as beam handling method and multilayer mirror lifetime.



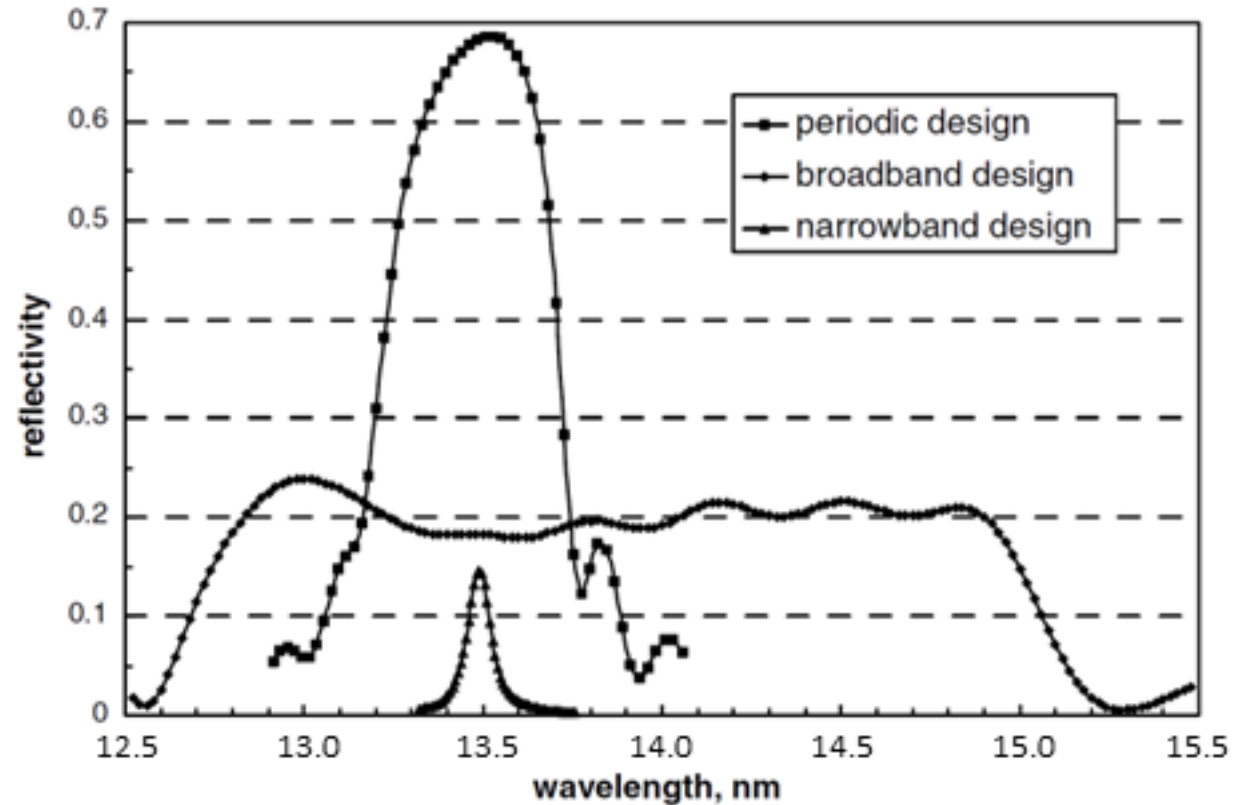


- NewSUBARU facility has a 1.0-1.5 GeV electron storage ring, which provides light beams from IR to Soft X-ray regions.
- We research light sources for next generation through a machine R&D, and industrial applications such as EUVL lithography, LIGA process, material analysis.
- 1GeV Top-up operation
- 1.5GeV Rumpup and decay operation



# Multilayer Mirror

- Mo/Si multilayer mirror
- In the long-wavelength soft X-ray region, especially in the 13 nm wavelength region, the direct incidence reflectance is up to about 70% by the Mo / Si multilayer film.



99.2 95.4 91.9 88.6 82.7 eV

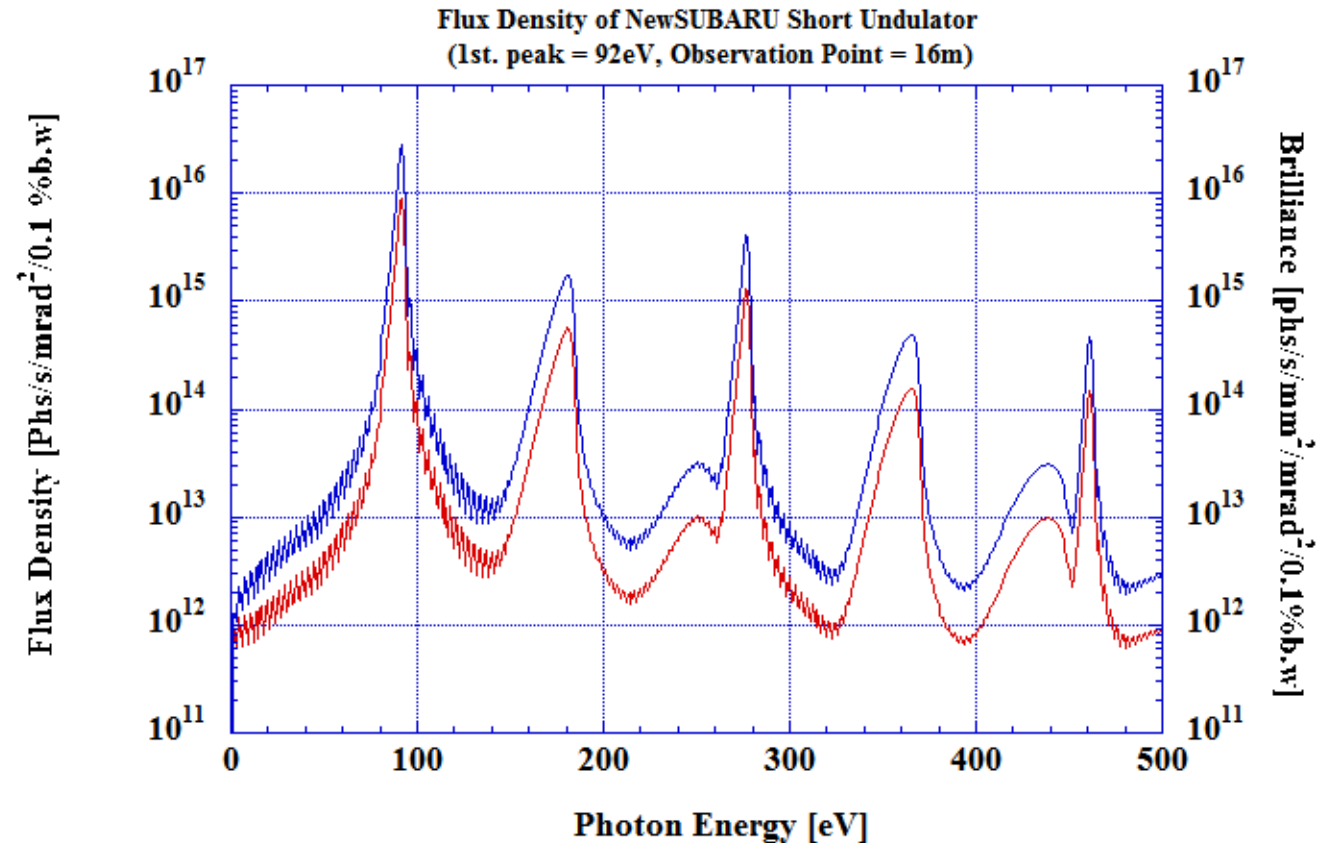
Mo/Si多層膜ミラーの反射率

(Microelectronic Engineering 83 (2006) 703.)

# Undulator spectrum at BL07 of NewSUBARU

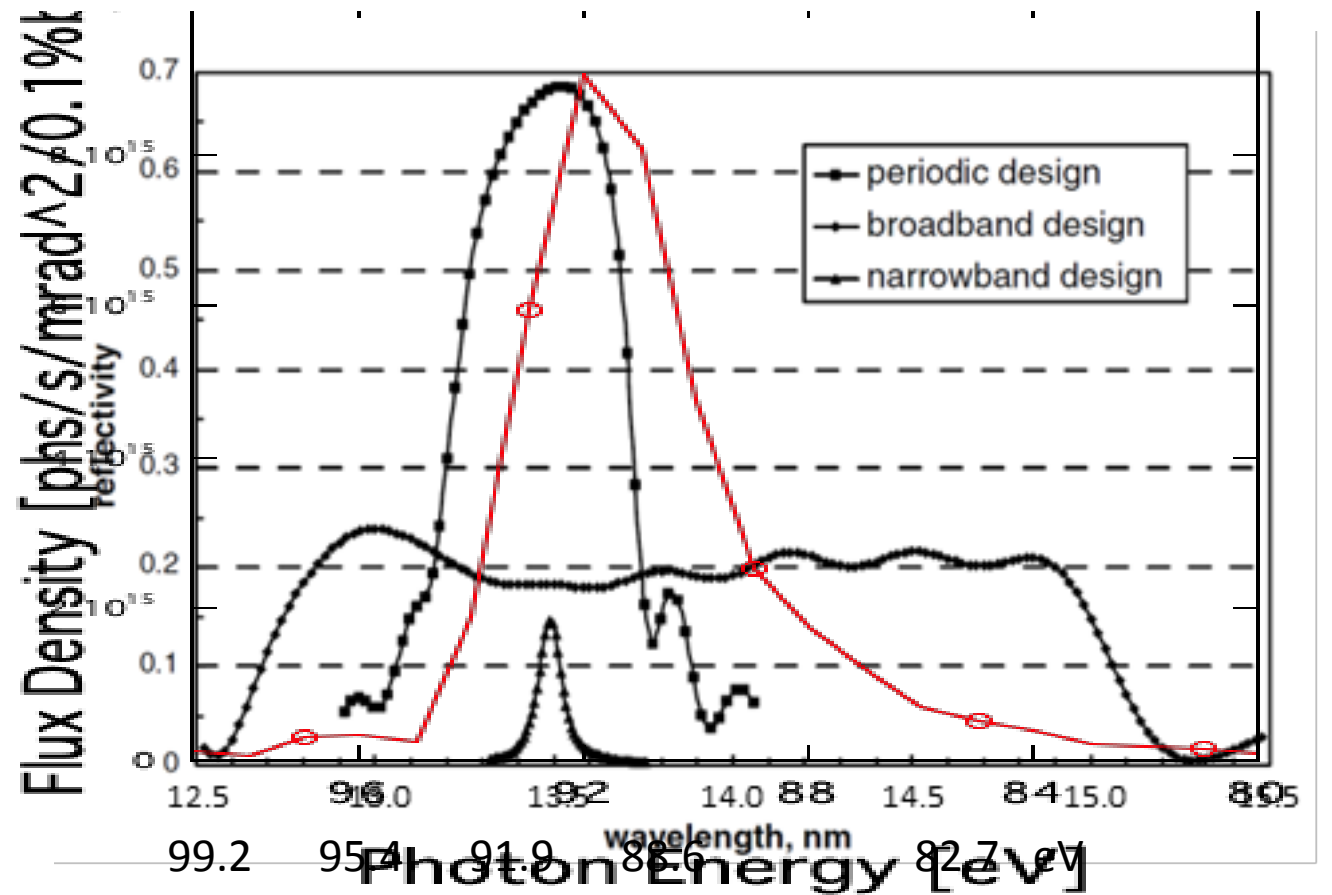
## Parameter

- Period length : 7.6 cm
- Number of Period: 30
- Total length :  $L = 2.28$  m
- $K = 0.78$
- Gap = 53.7 [mm]
- $B = 0.1099$  [T]



# Energy band Comparison of undulator and mirror

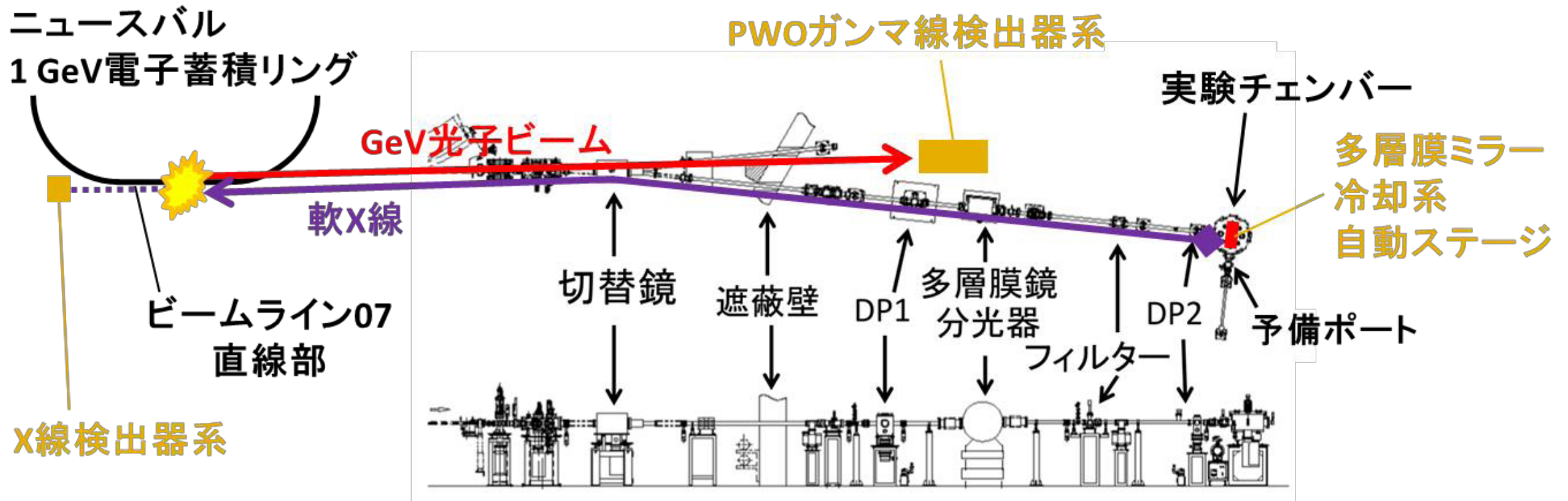
- $E \doteq 1240/\lambda$  [eV]
- $92\text{eV} = 13.47\text{nm}$



Mo/Si多層膜ミラーの反射率  
(Microelectronic Engineering 83 (2006) 703.)



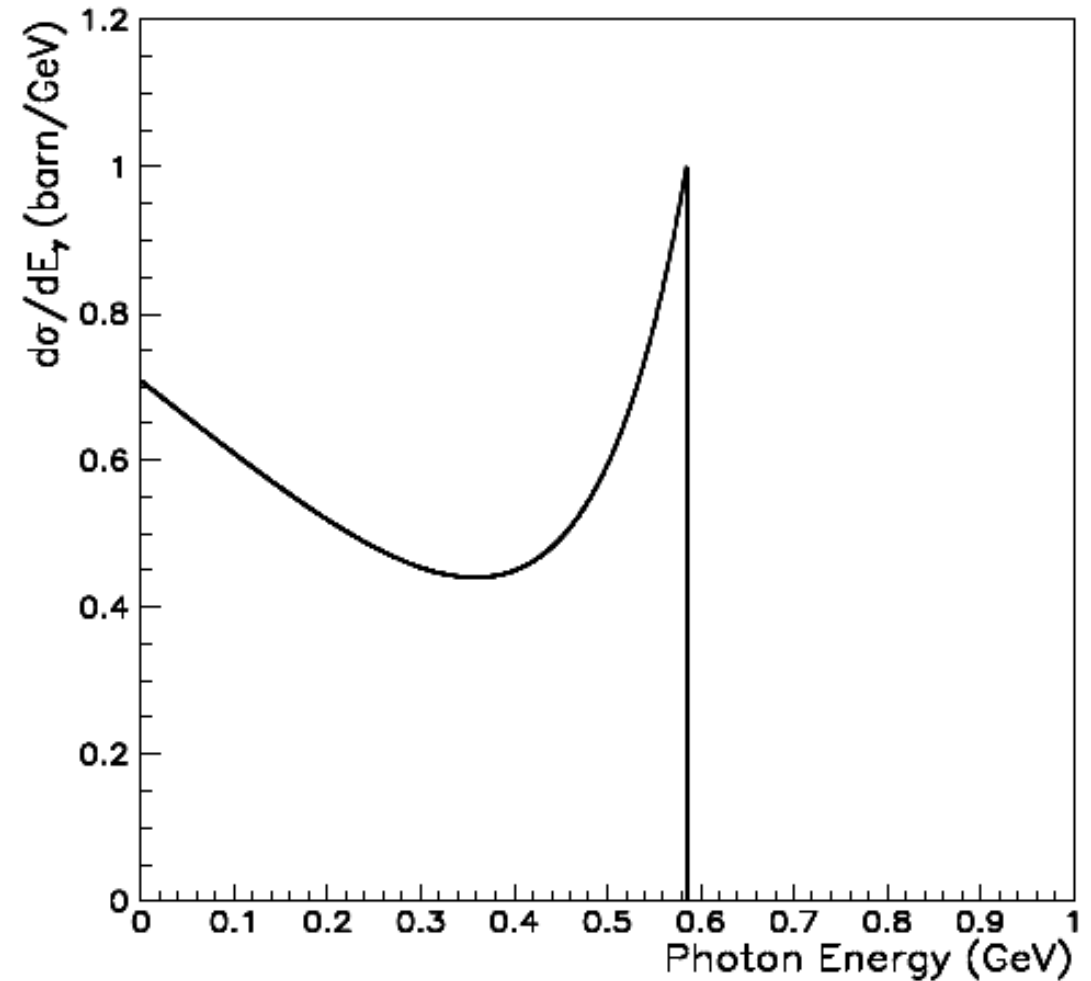
# Layout of experimental setup



ニュースバル・ビームライン07Aにおける実験セットアップ

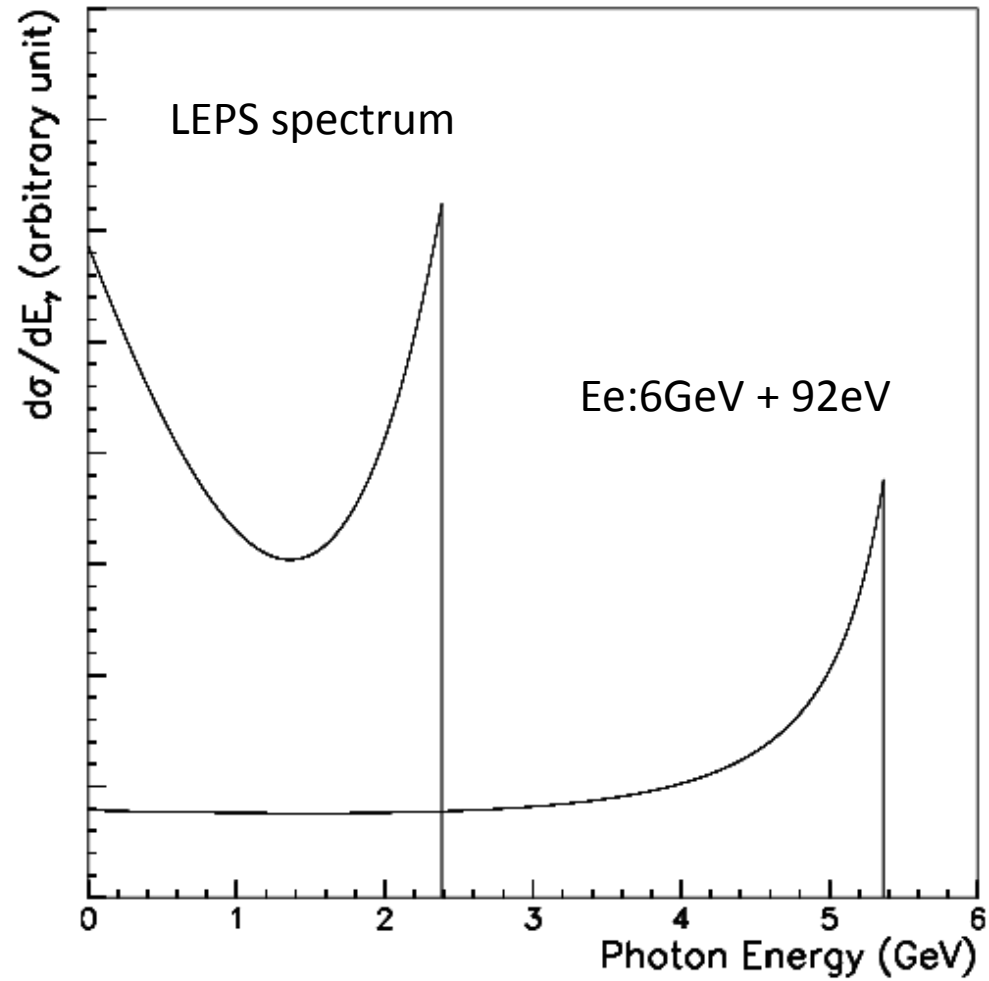
# $\gamma$ ray Spectrum

- 1GeV electron
- 92eV(13.5nm) Xray
- Compton edge 585MeV



$\gamma$  ray spectrum generated by inverse Compton scattering

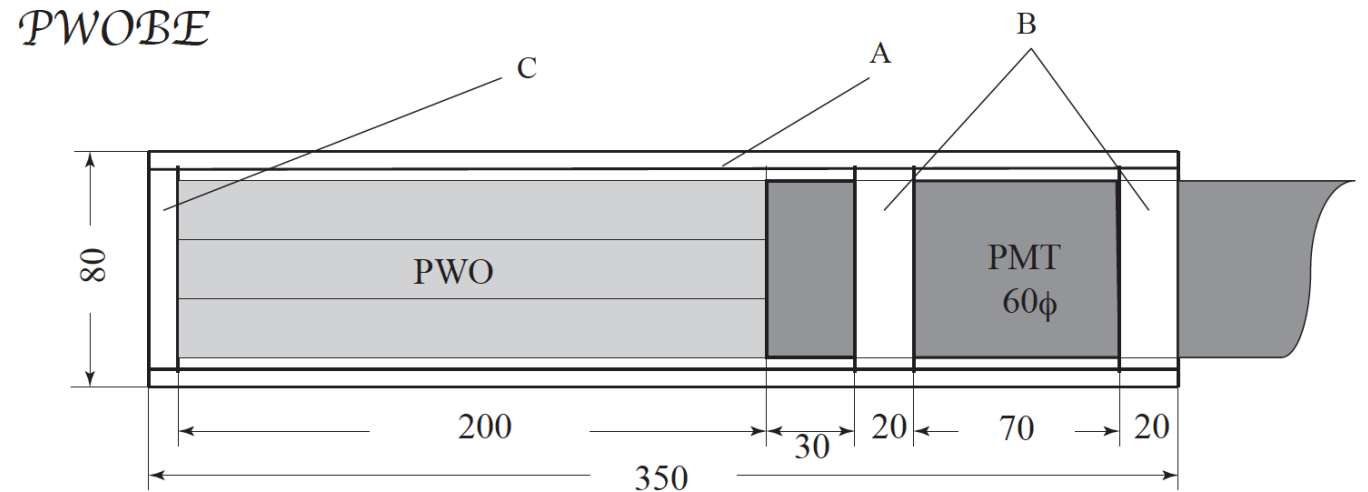
# Expansion to 6GeV



# $\gamma$ ray detector

- Trigger & Veto counter : 5 mm thick scintillator + PMT
- Beam position monitor (BPM)
- PWO detector

$\phi$  60 L200



# $\gamma$ photon counting rate

BL07 short undulator :  $5 \times 10^{15}$  photons/sec/mm<sup>2</sup>/mrad<sup>2</sup>/0.1% bw @ 100 mA  
Light source size :  $\sigma_x = 1.00$  mm、 $\sigma_y = 0.18$  mm  
X-ray divergence angle :  $\sigma_{x'} = 0.342$  mrad、 $\sigma_{y'} = 0.280$  mrad  
Primary light (undulator gap = 70 mm) band width / 0.1%BW@92 eV : 13 eV / 0.092 eV  
Switching mirror (Si substrate Pt coating) Reflectivity : 0.88  
 $\Rightarrow 3.21 \times 10^{16}$  photons/sec @300mA (on multicoating mirror)

Multicoating mirror BW : 2.7eV, Reflectivity : 0.65  
BW ratio  $\times$  reflectivity  $\times$  switching mirror reflectivity =  $2.7/13 \times 0.65 \times 0.88$  on colliding point  
Compton crosssection : 330 mb

Beamsize  $2\sigma_x = 2.00$  mm、 $2\sigma_y = 0.36$  mm。  
Undulator length : 3 m  
 $1.873 \times 10^{18}$  electrons/sec @300mA

$\Rightarrow 3300$  photons/sec

# Heat load

BL07 short undulator :  $15 \times 10^{15}$  photons/sec/mm<sup>2</sup> mrad<sup>2</sup>/0.1%bw @300 mA (1 GeV)

$\sigma_x = 1.0$  mm、 $\sigma_y = 0.18$  mm、 $\sigma_x' = 0.342$  mrad、 $\sigma_y' = 0.280$  mrad

0.1%bw =  $92$  eV  $\times$  0.1%

Full width at half maximum of primary light (gap 70 mm):  $81 \sim 94$  eV  $\Rightarrow$   $13$  eV

Switching mirror (Si substrate Pt coating): reflectance =  $0.88$

$\therefore$  The amount of light reaching the multilayer mirror

$$\begin{aligned} & (15 \times 10^{15}) \times 1.0 \text{ mm} \times 0.18 \text{ mm} \times 0.342 \text{ mrad} \times 0.280 \text{ mrad} \times (13 \text{ eV} / 0.092 \text{ eV}) \times 0.88 \\ & = 3.2 \times 10^{16} \text{ photons/sec} \end{aligned}$$

X-ray spectrum of BL 07 Integration of energy is  $4.65$  times of  $92$  eV light as a whole.

Total power :

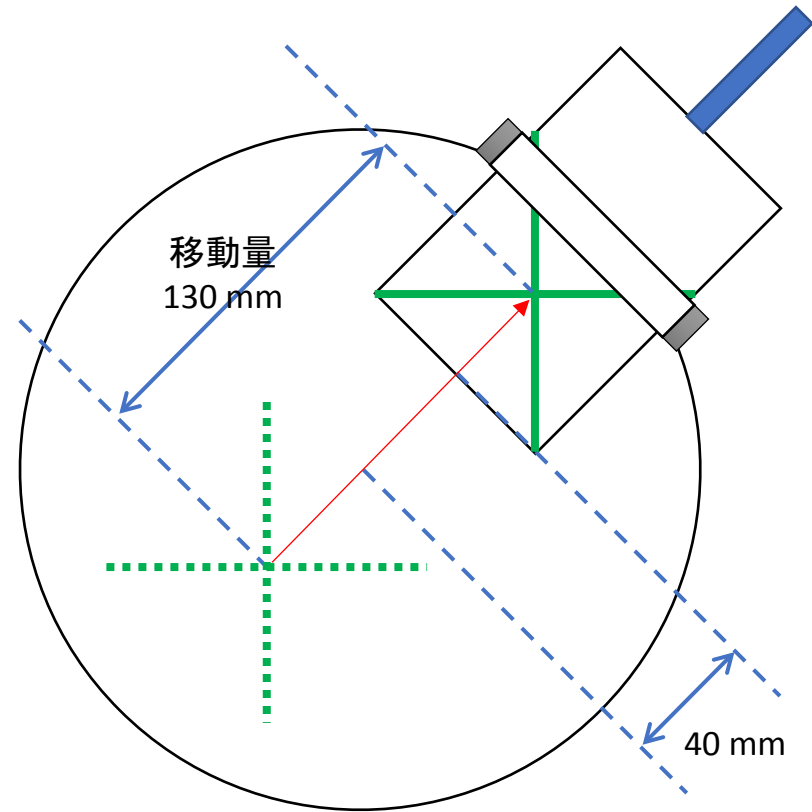
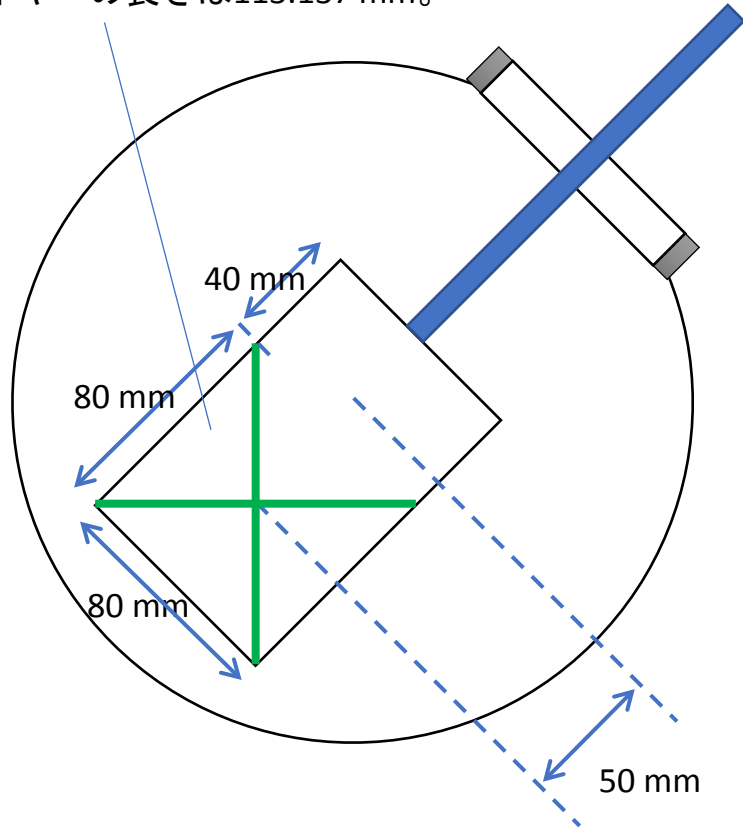
$$92 \text{ eV} \times (3.2 \times 10^{16} \text{ photons/sec}) \times 4.65 \times (1.602 \times 10^{-19} \text{ J/eV}) = 2.2 \text{ W}$$

**No problem with glass substrate**

# Problem

- Heat load, lifetime of the multilayer mirror
- Reflected X-ray handling, monitor

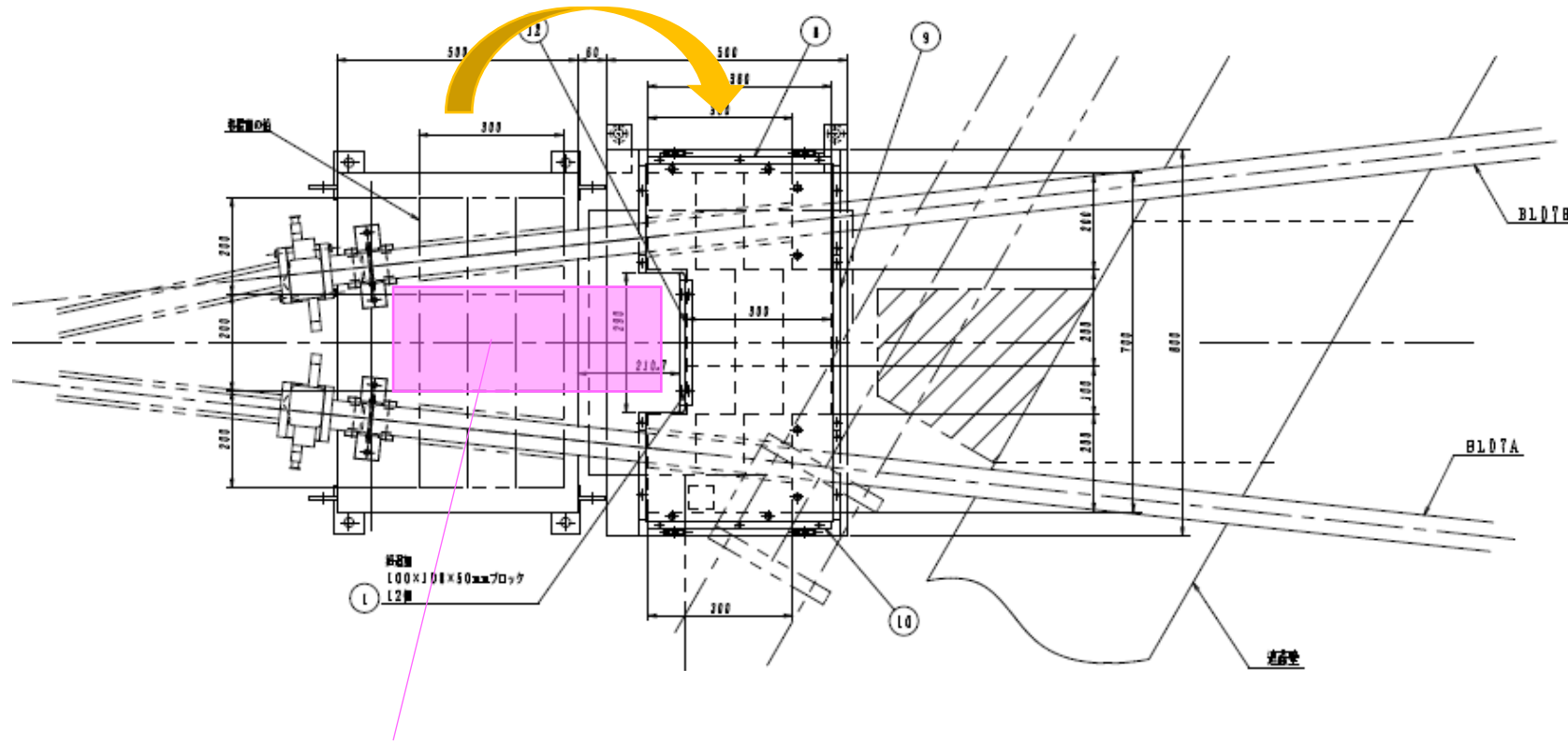
枠の内側を $80 \times (80+40)$ と仮定して計算。  
ワイヤーの長さは113.137 mm。





# 鉛遮蔽移設

約600 mm下流へ移動

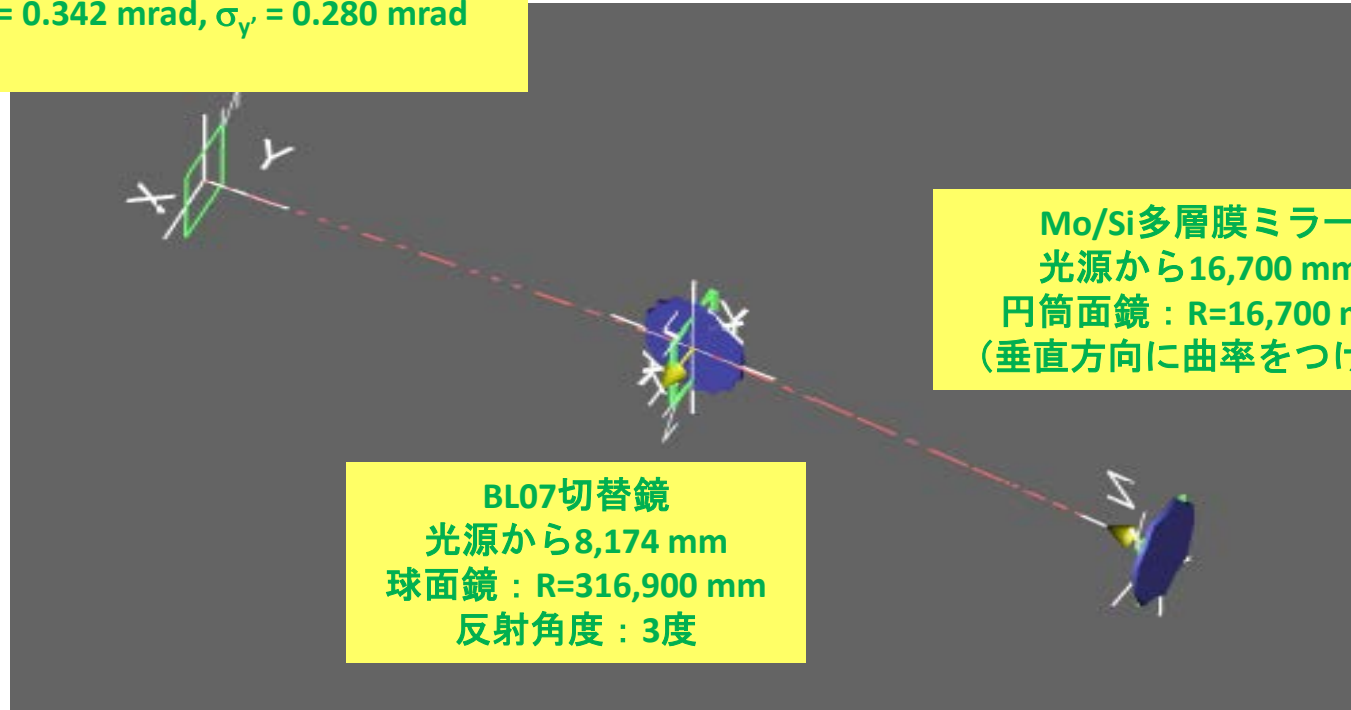


PWO電磁カロリメーター、BPM、  
トリガー・Vetoカウンターを設置。

3月下旬に工事（明昌）

# Ray Trace計算 (SHADOW3)

光源 (3 m短尺アンジュレーター)  
 $\sigma_x = 1.00 \text{ mm}$ ,  $\sigma_y = 0.18 \text{ mm}$ ,  
 $\sigma_{x'} = 0.342 \text{ mrad}$ ,  $\sigma_{y'} = 0.280 \text{ mrad}$

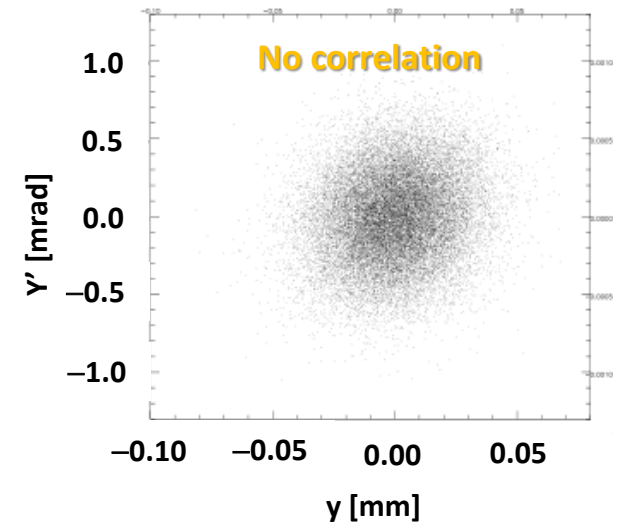
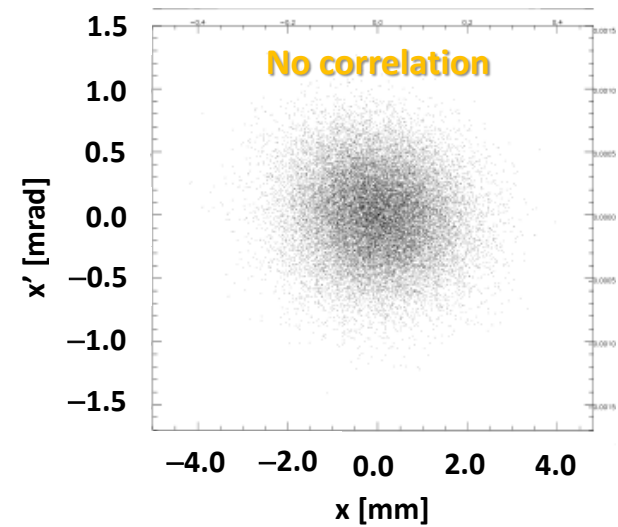
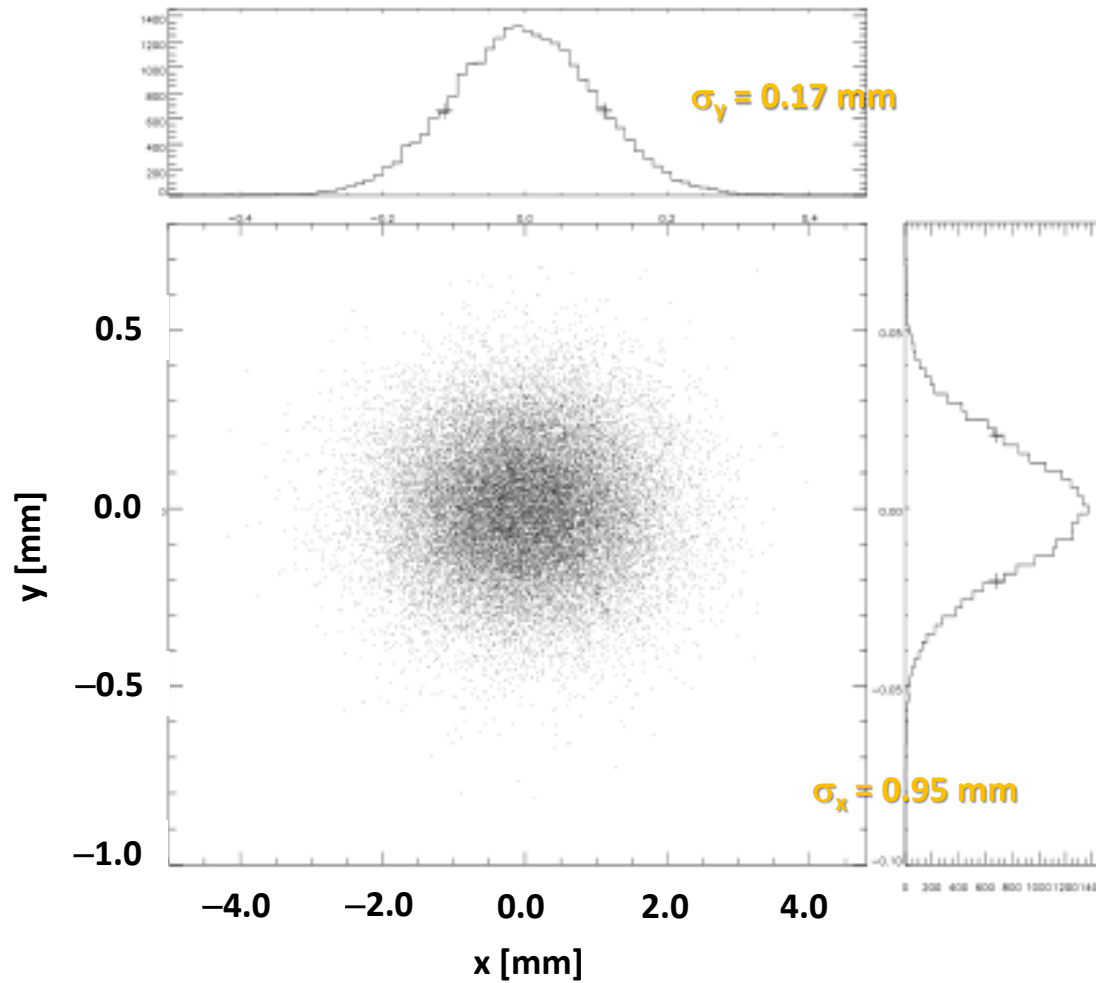


Mo/Si多層膜ミラー  
光源から16,700 mm  
円筒面鏡 :  $R=16,700 \text{ mm}$   
(垂直方向に曲率をつける)

BL07切替鏡  
光源から8,174 mm  
球面鏡 :  $R=316,900 \text{ mm}$   
反射角度 : 3度

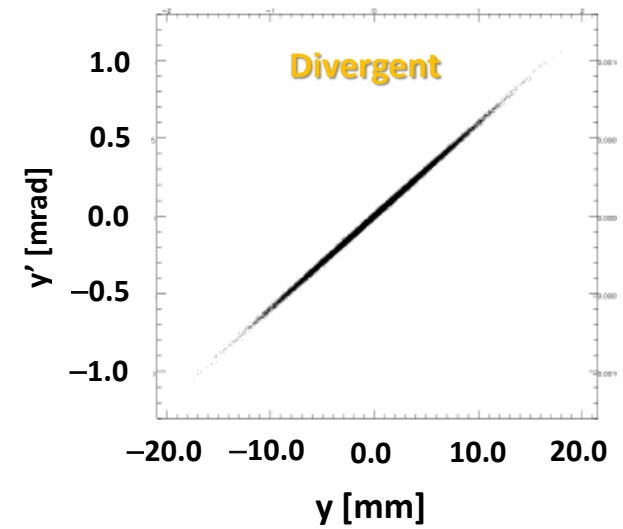
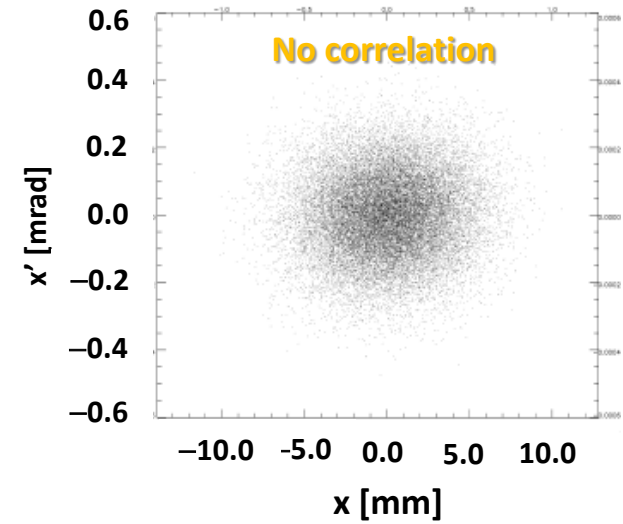
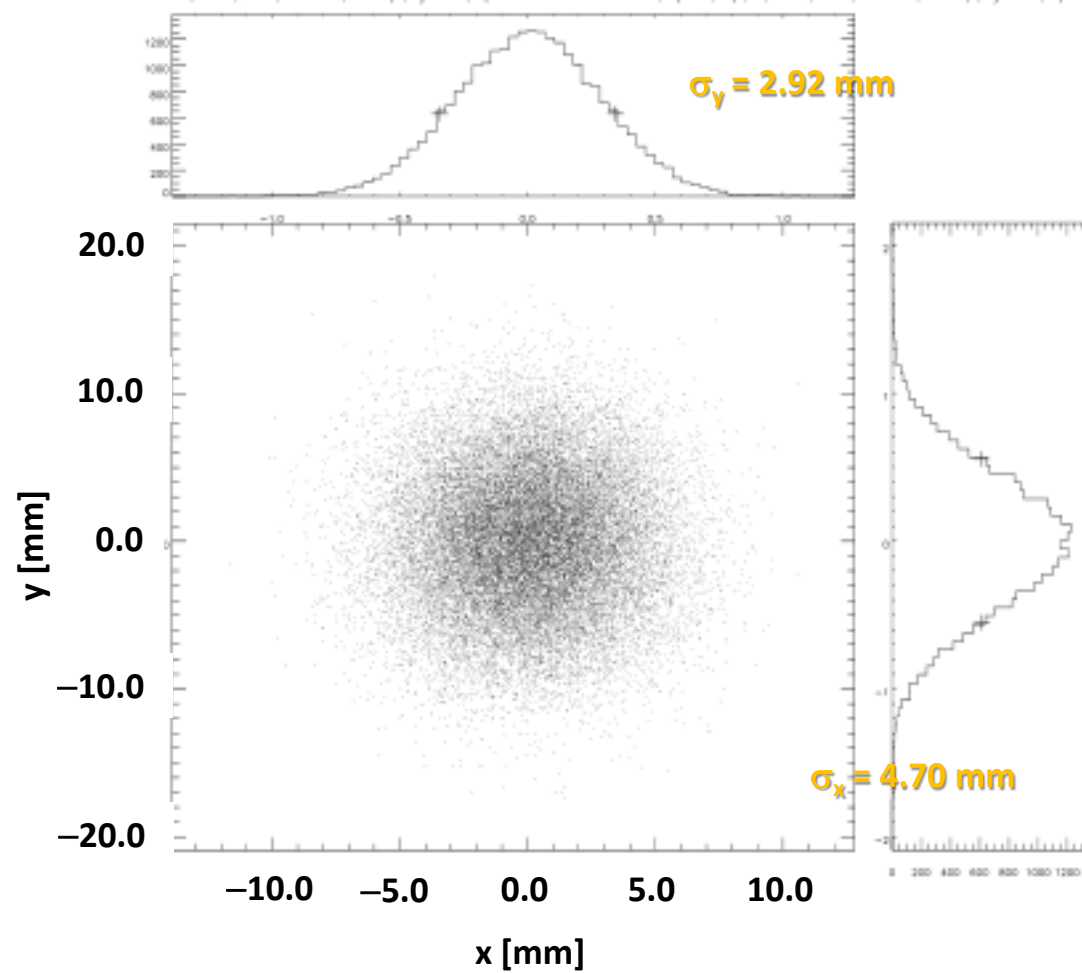
# 反射光焦点位置のビーム形状

Beam sizes are the same as those of the undulator output.



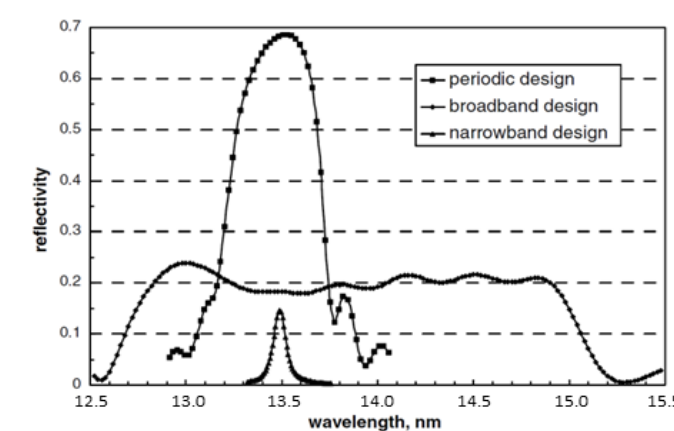
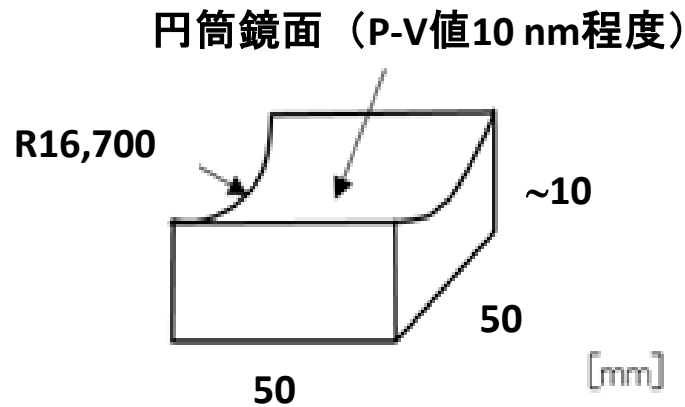
# 多層膜ミラー位置のビーム形状

Vertically divergent.  $\Rightarrow$  Need a cylindrical mirror.



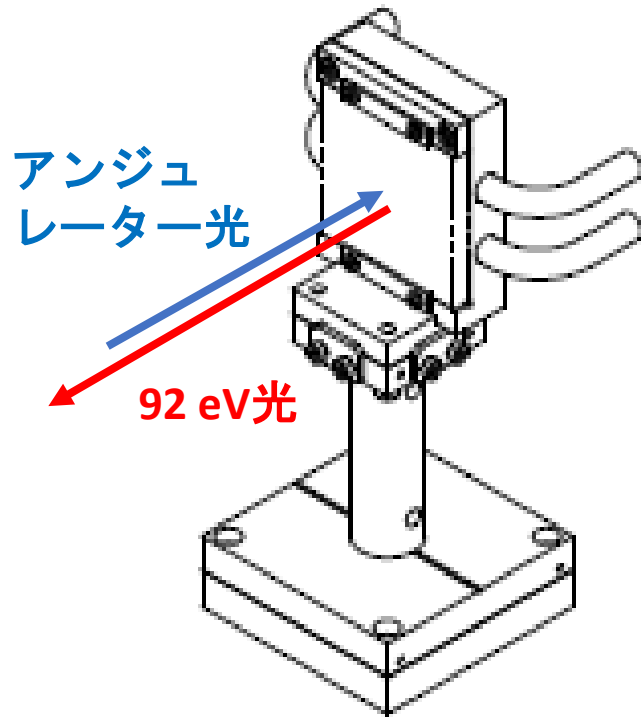
# 多層膜ミラーの製作

- 今年度は円筒鏡面ガラス基板の製作中  
低膨張ガラスZerodurからR=16700 mmの円筒面を作る（IK技研）  
機械掘削およびガラス曲げの2方法で進行中（岡部ポスター発表）  
P-V値：10 nm程度、表面粗さ：数nm
- 来年度、NTTアドバンステクノロジーにてMo/Si多層膜を形成予定。  
反射率：70%程度、帯域幅：0.5 nm程度 @92 eV



Mo/Si多層膜ミラーの反射率  
(Microelectronic Engineering 83 (2006) 703.)

## ミラーホルダー（来年度）



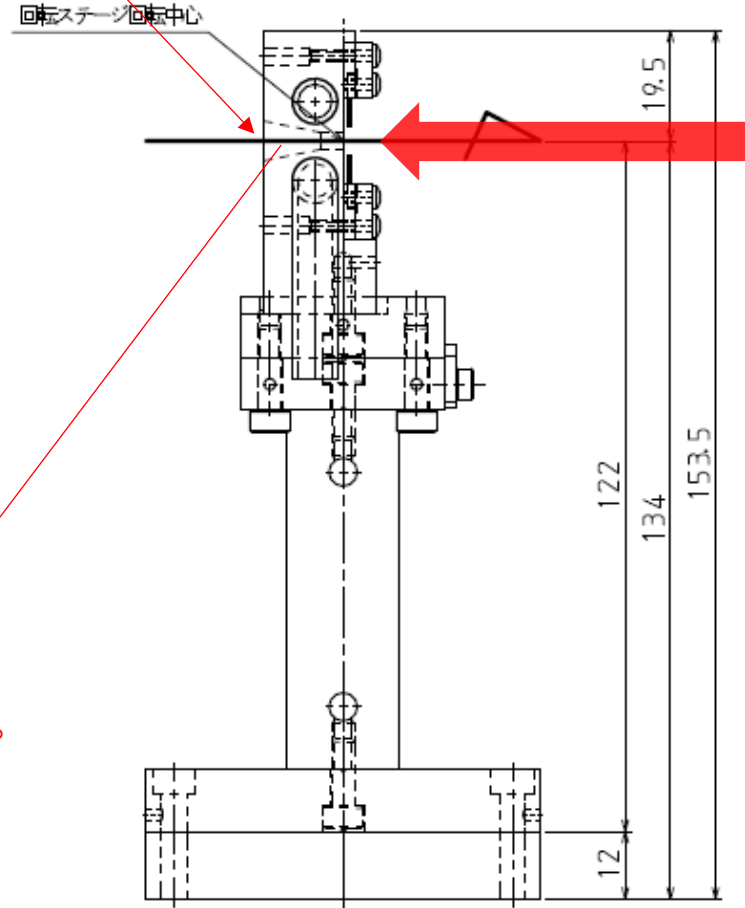
### 神津精機

- 硬X線実験（超高真空仕様）のものを改造  
⇒ 背面水冷配管と熱電対を付ける。
- 真空用ステッピング・モーター（回転、ゴニオ、高さ、水平）  
⇒ 硬X線実験のものを流用。
- BL07で他のユーザー実験を行う時は退避する。



回転ステージの回転中心が反射面になってほしい。今回は反射面がこの図面の右側。ミラーの厚さは前ページの通り15 mm。

ホルダーの温度を測りたいので、熱電対を圧着端子に付けてホルダー背面にねじ止めしたいと考えています。背面にM4のタップを切って頂きたい。



今回はX線の入射方向が赤矢印のように逆になる。

この穴は要らない。

質問：納期と値段はどれくらいになるでしょうか？（予算次第で来年度の可能性もあります。）